PATENT ABSTRACTS OF JAPAN

(11)Publication number:

01-132767

(43) Date of publication of application: 25.05.1989

(51)Int.CI.

C23C 14/54

(21)Application number: 62-292368

(22)Date of filing:

62-292368 19.11.1987 (71)Applicant:

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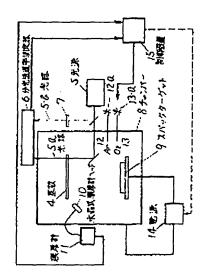
(54) METHOD AND DEVICE FOR FORMING THIN FILM

(57) Abstract:

PURPOSE: To form a film having stable characteristics and to improve the quality of the film by obtaining the information on the compsn. of the film from the information on the transmittance of a thin film under formation and the information on the thickness of the film and controlling

film forming conditions.

CONSTITUTION: Of the light emitted from a light source 5, the light of an optical path 5a past a <u>substrate 4</u> under film formation and the light of an optical path 5b past a <u>reference substrate 7</u> are put into a <u>spectral transmittance</u> measuring instrument 6 which measures the <u>transmittance</u> of the <u>vapor deposited film</u> from the ratio of both the transmitted light beams. On the other hand, the rate of the target material splashing from the <u>target 10</u> is monitored and the film thickness is measured by a quartz type film thickness gage head 10 of a film thickness gage 11. The information of the film thickness gage 11 and the information from the spectral transmittance measuring instrument 6 are inputted to a <u>control device 15</u>. The flow rate of oxygen or sputtering power is controlled in accordance with this information by the control device 15, by which the compsn. of the thin film is controlled to the desired compsn.



Sputtering!

LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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